

**The New Generation Laser Dicing
Technology for Ultra Thin Si wafer**

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New Generation Laser Dicing Technology for Ultra Thin Si Wafer

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Background

◆ INHERENT PROBLEM of BLADE DICING

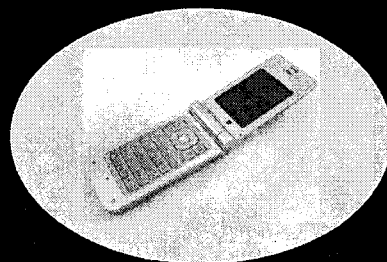
- undesirable mechanical stress

> It is difficult that dicing processing speed become higher or wafer thickness become thinner.

But, Wafer will be thinner

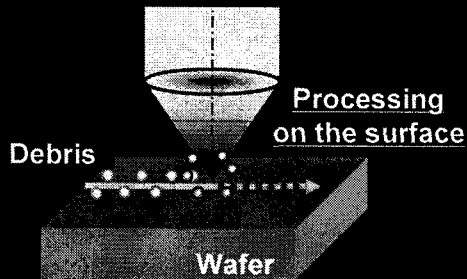
100 μm \Rightarrow 50 μm \Rightarrow 30 μm

>>> LASER DICING!!



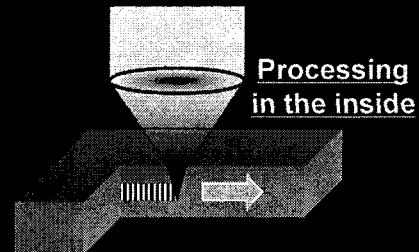
Laser Dicing

Ablation method



- Debris contamination
- Cleaning process
- Cut loss

Stealth Dicing (SD)



- No debris contamination
- No cleaning process
- Less cut loss



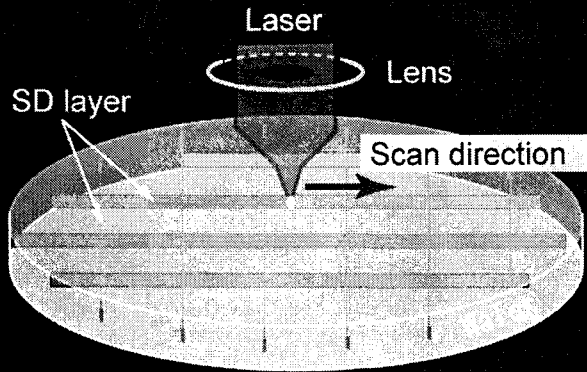
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Advantages of SD

1. High Speed dicing for thinner wafers without chipping.
2. No debris contaminants and no creating damages on the surface.
3. Completely dry process.

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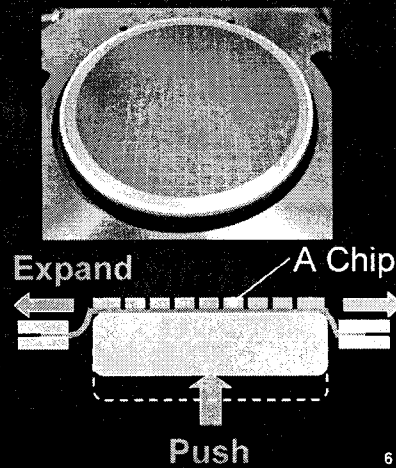
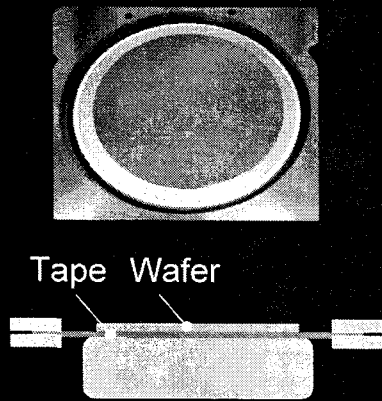
Stealth Dicing Process (1st Step: Laser Processing)



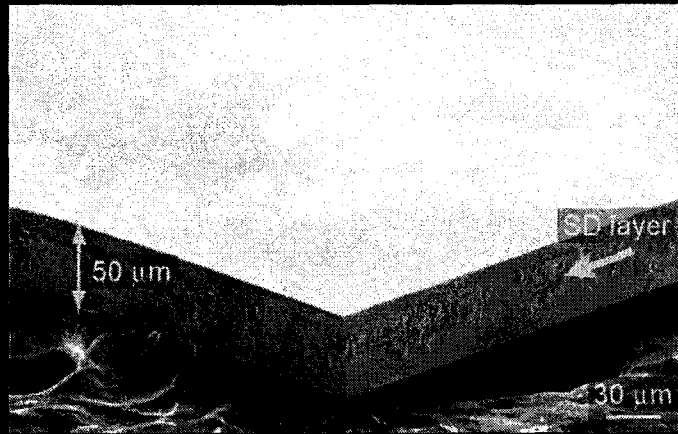
Stealth Dicing Process (2nd Step: Wafer Separation)

Before tape expansion

After tape expansion



Cutting Edge Quality

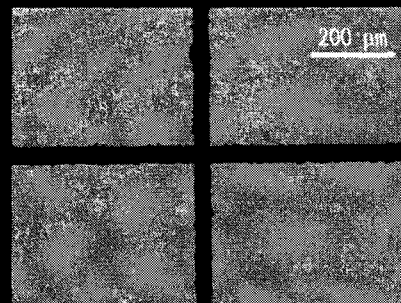
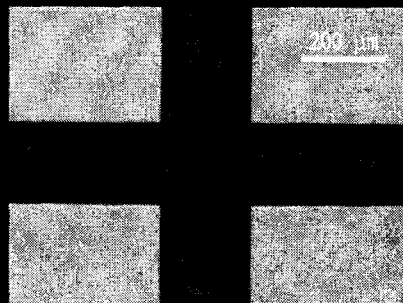


SEM image of cutting edge by SD

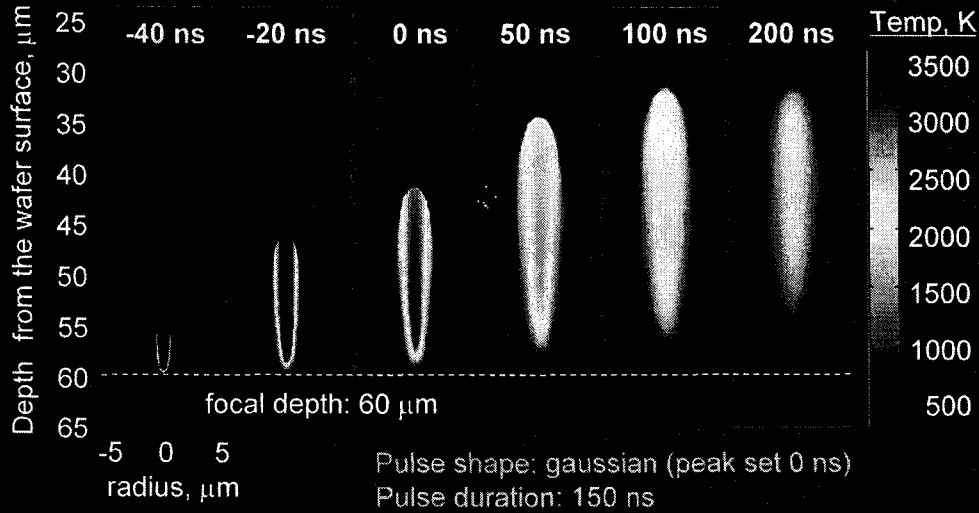
Cutting Edge Quality

■ Stealth dicing (top view)

■ Blade dicing (top view)



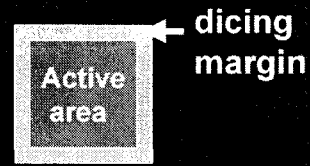
Processing Mechanism



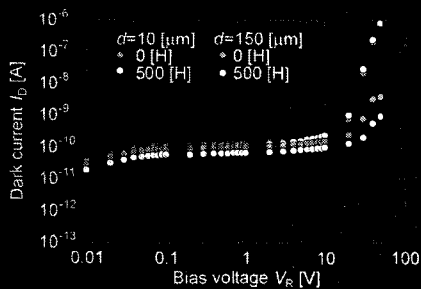
Reported by E. Ohmura *et al.* (2006) 9

Device Characteristics

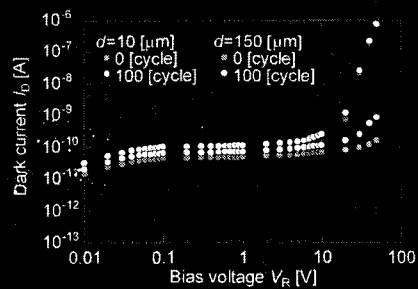
- **BHT test**
12 [V], 85 [%], 85 [°C]; 0~500 [H]
- **TC test**
-55°C~125°C; 0~100 [cycle]



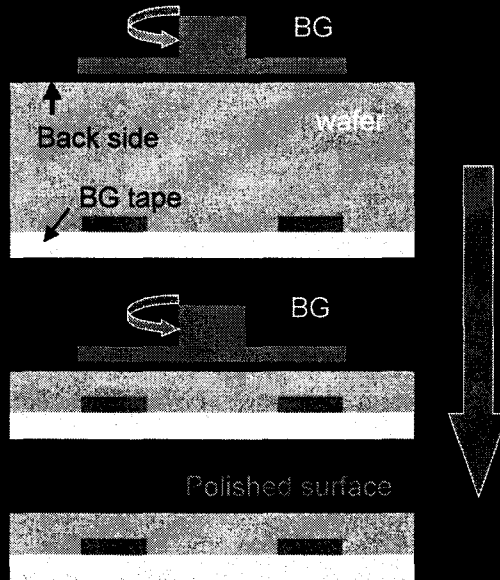
BHT test



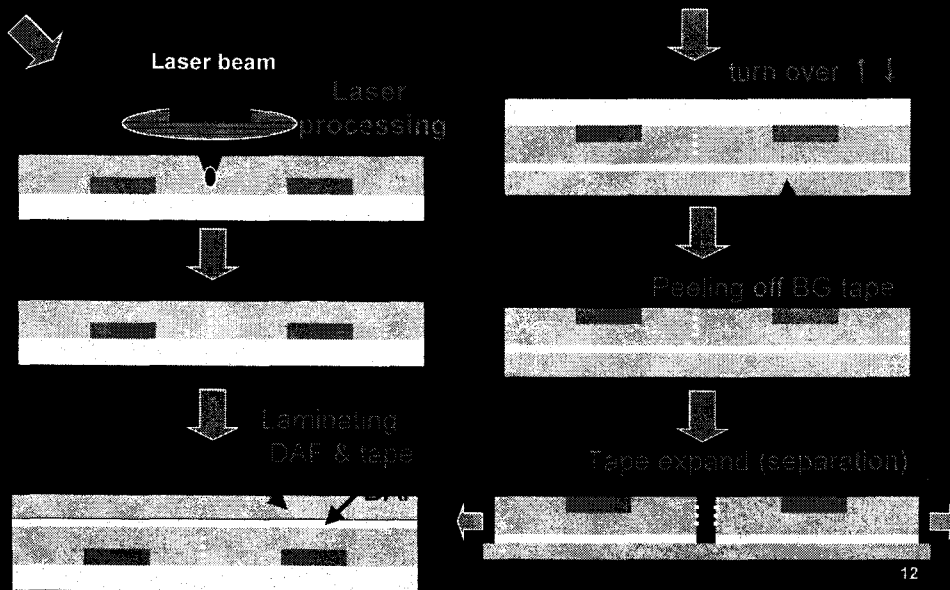
TC test



Application for a DAF



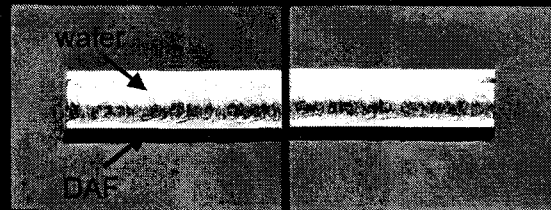
Application for a DAF



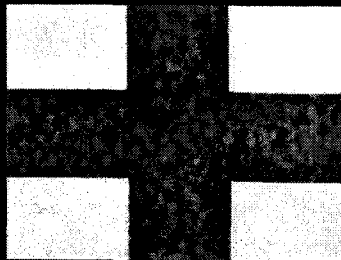
Application for a DAF

- Wafer size : 8 inch
- Wafer thickness: 100 μm
- DAF thickness : 25 μm

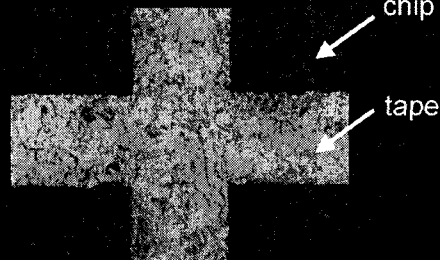
Cross Section



Front side



Back Side



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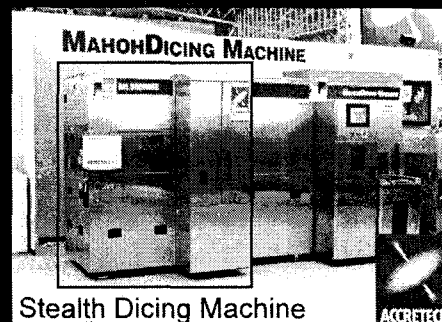
Stealth Dicing Machine

➤ Mahoh dicing machine, which is the brand name of ACCRETECH, is a Stealth dicing machine with built in Stealth Dicing Engine (SDE) which is made by HAMAMATSU PHOTONICS.

In-line system components for 12 inch

- Mahoh Dicing Machine (SDE inside)
- UV Irradiator
- Tape mounter & Tape Expander

*This system is provided by ACCRETECH



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Summary

Process & mechanism

- ◆ The process consists from two steps which are laser processing step and separation step.
- ◆ The wavelength of laser beam is transmissible wavelength for the wafer. However, inside of Si wafer is processed due to temperature dependence of optical absorption coefficient

Summary

Advantage & Application

- ◆ Advantages are high speed dicing, no debris contaminants, completely dry process, etc.
- ◆ The cutting edges were fine. The lifetime and endurances did not degrade the device characteristics
- ◆ A separation of a wafer with DAF was introduced as an application for SiP